Electron transport in graphene

"Graphene = a material for future electronics"

- Conductivity & mobility in graphene
 - Drude picture
 - Effective mass
 - Boltzmann equation
- Scattering mechanisms, limitation of mobility
- Present status
- Applications

"Dirac physics" in transport

- Klein tunneling
- Reflectionless transmission in p-n junction
- Evidence of Klein backscattering in interference pattern of n-p-n junction

Graphene based Hybrid Quantum Devices

Sources:

http://www.tntconf.org/2010/Presentaciones/TNT2010 Geim.pdf

Conductivity, mobility

Mobility, conductance:

$$v_d \equiv \mu E$$

 $j \equiv env_d = en\mu E = \sigma E \quad \sigma = en\mu$

Conductivity (Drude model):

$$\sigma = \frac{e^2 n\tau}{m} \qquad \mu = \frac{e\tau}{m}$$

How to separate mobility (μ) and e density (n)?

Measure: ρ + Hall resistance $R_H = \frac{E_y}{j_x B} = -\frac{1}{ne}$

Effect of gate voltage, V_g?

$$N = C_g V_g / e \rightarrow n \sim V_g \rightarrow k_F \sim \sqrt{V_g}$$

Measurement:

- At V_g zero, R_H (and n) changes sign \rightarrow boarder between e and h bands - mobility largest at Dirac point (V_g = 0).



graphene

R vs. V_a Transport characteristics



Conductivity, mobility

How to calculate conductivity?

$$\sigma = e^2 \tau \frac{n}{m}$$

What is m, effective mass?

 $\frac{1}{m} = \frac{1}{m_{xx}} = \frac{1}{\hbar^2} \frac{\partial^2 E}{\partial k_x^2}$

For quadratic dispersion: $E = \frac{\hbar^2 k^2}{2m_{eff}}$, $m = m_{eff}$

For Dirac electrons, where $E(\vec{k}) = \hbar v_F |\vec{k}|$? Naively 1/m= 0, but NOT.

To calculate 1/m:

$$\frac{\partial^2 |k|}{\partial k_x^2} = \dots = \frac{k_y^2}{|k|^3} \rightarrow \frac{1}{m_{xx}} = \frac{1}{\hbar} v_F \frac{k_y^2}{k^3}$$
$$\frac{\partial |k|}{\partial k_x} = \frac{1}{2} \frac{2k_x}{|k|}$$

→ Effective mass depends on k

One has to average 1/m for all filled states:

$$E(\vec{k}) = \hbar v_F |\vec{k}|$$



 E_F

n

Conductivity, mobility

Accurate calculation of σ ?

From Boltzmann equation (see Solyom 24.3.39.):

$$\sigma = e^2 \tau \frac{n}{m} = e^2 \tau \cdot 2 \cdot 2 \cdot \int_{filled \ k \ states} \frac{d^2 k}{(2\pi)^2} \frac{1}{m_{xx}}$$

HOMEWORK Calculate σ

Result:

$$\sigma = e^2 \tau \frac{v_F}{\hbar \pi} k_F$$

with relaxation length $l \equiv v_F \tau$

$$\sigma = \frac{2e^2}{h} lk_F$$

Ū

 E_F

Mean free path:

$$=\frac{\hbar}{e}\mu\sqrt{n\pi}$$

E.g. for mobility =600.000, I is only $\approx 3 \mu m$

$$E(\vec{k}) = \hbar v_F |\vec{k}|$$



Nature 438, 201 (2005)

What limits the mobility at room T?

Source of $1/\tau$?

Scattering mechanisms resulting resistivity:

- potential scattering: impurities, defects, vacancies
- Electron phonon scattering

- Etc.

Usual terms: (see Solyom II.)

- Residual resistivity (ρ_0): T independent
- Longitudinal acoustic phonons (ρ_A): linear in T

$$\rho(V_{\rm g},T) = \rho_0(V_{\rm g}) + \rho_{\rm A}(T); \quad \rho_{\rm A}(T) = \left(\frac{h}{e^2}\right) \frac{\pi^2 D_{\rm A}^2 k_{\rm B} T}{2h^2 \rho_{\rm s} v_{\rm s}^2 v_{\rm F}^2}$$

Measurements (see Fig. a,b)

- At higher T, strong deviation from linear T dependence

- Dependence also on Vg

 \rightarrow It suggests scattering on high energy phonon modes



$$\begin{split} \rho(V_{\rm g},T) &= \rho_0(V_{\rm g}) + \rho_{\rm A}(T) + \rho_{\rm B}(V_{\rm g},T);\\ \rho_{\rm B}(V_{\rm g},T) &= B_1 V_{\rm g}^{-\alpha_1} \left(\frac{1}{e^{(59\,{\rm meV})/k_{\rm B}T}-1} + \frac{6.5}{e^{(155\,{\rm meV})/k_{\rm B}T}-1} \right) \end{split}$$

 ρ_B : additional term to fit the measurements (see Fig. c,d) Bose-Einstein distribution ~ population of high energy phonon modes, e.g. optical phonons Very good fit of the measured curves with alfa=1.04

Optical phonons of graphene?

- Strong Vg dependence is not expected

- Mainly out of plane phonons at this energy. It is not expected to give strong contribution

Interfacial phonon scattering: Surface optical phonon modes in SiO₂ couples to e-s in graphene The expected phonon energies and coupling strength (1:6.5) are inserted into ρ_B Strong Vg dependence also expected



What limits the mobility at room T?

Different T dependence of ρ_0 , ρ_A , ρ_B allows to separate the three contributions. ($\rho_B = \rho - \rho_0 - \rho_A$)

Fig. a

 $ho_{A} V_{g}$ independent $ho_{B} \sim V_{g}^{i-1.04}$ relation confirmed

\rightarrow Residual resistivity dominates

Fig. b

Derive the mobility related to two e-p processes :

 μ = 1/ne ρ = 1/c_gV_ge ρ

 \rightarrow SiO₂ contribution (c) dominates

→ The intrinsic, LA phonon scattering mobility at $n=10^{12}$ cm⁻² (technologically relevant) : $\mu \approx 200\ 000$

(see blue dot) Higher than any known semiconductor!

(E.g. InSb \approx 77 000 and carbon nanotubes \approx 100 000).

Contributions at Room T



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Fig. a $\rho_A V_g$ independent $\rho_B \sim V_g^{i-1.04}$ relation confirmed \rightarrow Residual resistivity dominates u (cm² V⁻¹ s⁻¹) Fig. b Derive the mobility related to two e-p processes : μ = 1/ne ρ = 1/c_gV_ge ρ \rightarrow SiO₂ contribution (c) dominates \rightarrow The intrinsic, LA phonon scattering mobility at n= 10^{12} cm⁻² (technologically relevant) : $\mu \approx 200\ 000$ (see blue dot) Higher than any known semiconductor! (E.g. InSb \approx 77 000 and carbon nanotubes \approx 100 000). Fig. c

C 0⁶

T dependence



Comparision with graphites, sources of exfoliated graphene

Mobility is much smaller than for graphites. It is impurity dominated.

 \rightarrow Residual res. not due to point defects

but due to charge impurities in SiO_{2 substrate}

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T dependence



Σ: Problem, SiO₂ is bad substrate

Suspended flakes

SiO is etched by BHF



mobility up to 200,000cm²/V's Mean free path L $\sim \mu m$

low-T mobilities few million cm²/V[•]s Manchester, arxiv 2010

 \rightarrow Demostration of FQHE

PMGI based organic polymer N. Tombros <u>arXiv:1009.4213</u>



Possible with any metals -> spin physics, supercondcutivity 600.000 cm2/Vs at n = 5.0 E9 cm-2 at 77K. L~3µm

Suspended flakes

SiO is etched by BHF

PMGI based organic polymer N. Tombros <u>arXiv:1009.4213</u>



mobility up to 200,000cm²/V's Mean free path L ~ μ m

low-T mobilities few million cm²/V[•]s Manchester, arxiv 2010



LOR

SiO₂ n* Si

Ç.







 \rightarrow Demostration of FQHE

Better substrate – Boron Nitride





room-T mobility close to 100,000 cm2/V[·]s

because it has an atomically smooth surface that is relatively free of dangling bonds and charge traps. It also has a lattice constant similar to that of graphite, and has large optical phonon modes and a large electrical bandgap.



Dean et. al., NatureNanotech 5, 722 (2010)

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Band structure

Lattice, reciproce lattice Unit cell with two atoms A and B sublattice





Grafén tight binding sávszerkezeti leírása: Első szomszéd hopping közelítésben (csak másik alrácsra ugorhat az elektron) Hamilton 2*2 mátrix, A és B alrács komponensekre:

$H=v_F \sigma \bullet p$

ahol σ a Pauli mátrixok, p az e. impulzusa, v_F ≈ 10⁶m/s
A két alrács pseudospinként viselkedik:
|↑> : A alrácson tartózkodás (zöld)
|↓> : B alrácson tartózkodás (piros)
→ Formailag a Dirac egyenlettel megegyező leírást, ahol spin szerepét átveszi a pszeudospin



Tunneling, Klein tunneling



Beenakker, Reviews of Modern Physics, 80, 1337 (2008)

Geim, Kim, Sci.Am. 298, 90 (2008)

Tunneling, Klein Backscattering

$$\frac{1}{m_{xx}} = \frac{v_F}{\hbar} \frac{k_y^2}{|k|^3}$$

Evolution of group velocity:

$$\frac{dv_x}{dt} \equiv \frac{1}{m_{xx}} F_x = \frac{1}{m_{xx}} (-e) E_0 \quad (*)$$

In linear electrostatic potential:

$$V = E_0 x, \quad E_x = E_0, \quad F_x = -eE_0$$

At normal incident: $k_y = 0 \rightarrow \frac{dv_x}{dt} = 0 \rightarrow$ backscattering is avoided

Electron can propagate through an infinite high potential barrier.

Klein scattering:

perfect transmission at normal incident

N-P junction: Potential profile with a step of U₀ at a distance d



Beenakker, Reviews of Modern Physics, 80, 1337 (2008)

Tunneling, Klein tunneling

More precisely, quasi classical dynamics

Two Dirac cones: Conduction band $E = \hbar v_F |k|$, Valance band $E = -\hbar v_F |k|$, $\vec{v} \equiv \frac{1}{\hbar} \frac{\partial E}{\partial \vec{k}} = \frac{1}{\hbar} \hbar v_F \frac{\vec{k}}{|k|} = v_F \overline{e_k} = v_F^2 \frac{\vec{k}}{F}$,

$$\vec{v} \equiv \frac{1}{\hbar} \frac{\partial E}{\partial \vec{k}} = \frac{1}{\hbar} \hbar v_F \frac{\kappa}{|k|} = v_F \overline{e_k} = v_F^2 \frac{1}{h}$$

thus $|v| = v_F, \vec{v} ||\vec{k}|$

N-P junction: Potential profile with a step of Uo at a distance d



$$\hbar \dot{\vec{k}} \equiv \vec{F} = -eE_0 \overrightarrow{e_x}$$

Effect of the potential profile, U (see figure):

- k decreases and changes sign
- based on (*), \vec{v} stays constant, i.e. $\vec{v} = v_F \vec{e_x}$.
- ightarrow e ends up in the valence band

Klein scattering:

perfect transmission at normal incident

Beenakker, Reviews of Modern Physics, 80, 1337 (2008)

Tunneling, Klein tunneling

Result of proper calculation

Wave function matching

60°

a 1.0 00

0.8

0.6

0.4

0.2

0

0.2

0.4

0.6

0.8

1.0



Transmission probability vs. D

of normally incident electrons - in single- and bi-layer graphene (red and blue curves, respectively) and in a non-chiral zero-gap semiconductor (green curve)



Trans throu barri incid barri

Transmission probability T

through a 100-nm-wide barrier as a function of the incident angle, two different barrier height

 \rightarrow Difficult to measure since e-s out of normal incident also arrive

Katsnelson et al Nature Physics, 2, 620 (2006)



Backscattering on P-N-P junction

When incident angle, α is varied from positive to negative, phase of the reflection amplitude (R) jumps π . Its sign changes. (At α =0, R=0).

If $\alpha <>0 \rightarrow R>0$, several scatterings in P-N-P \rightarrow interference pattern Accumulated phase in one circle: $\Delta \theta = 2\theta_{WBK} + \Delta \theta_1 + \Delta \theta_2$ where θ_{WBK} phase from travelling in N $\Delta \theta_1, \Delta \theta_2$ Klein backreflection phase of the interfaces

At B=0 (see Fig. a) the incident angles

 $\Delta \theta_{1(2)}$ at P-N and N-P have opposite signs \rightarrow jumps in $\Delta \theta_1$, $\Delta \theta_2$ cancels

At B>0 (see Fig. b), trajectories are curved, \rightarrow incident angles at P-N and N-P can be equal In this case one can show that $\Delta \theta_1 + \Delta \theta_2 = \pi$ (It is a Barry phase!) Thus for B=0 \nearrow and trajectories with small p_y π shift is expected (i.e. sign change) transmission amplitude

(Fig.c) one can show, it is robust against barrier roughness Shytov et al. PRL 101, 156804 (2008)



Shytov et al. PRL 101, 156804 (2008)

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N-P-N device

Separate gating by backgate and topgate Topgate width=20nm! \rightarrow ballistic





G vs. Vtg vs. Vbg

Conductance is lower when N-P-N setting instead of N-N-N
Oscillations at N-P-N configuration:

> - V_{TG} varies pot. barrier \rightarrow $\theta_{WBK} \rightarrow$ oscillations -Oscillatory G is induced by trajectories with incident angle where neither T, nor R is large (i.e. α not too small)





N-P-N device

а

Separate gating by backgate and topgate Topgate width= $20nm! \rightarrow ballistic$ **G oscillations vs. B** (*Dots experiment, line theory*) At different B fields (B=0, 200, 400, 600, 800mT) the oscillations of G. In this B range $\approx \pi$ shift is induced in the interference patern.





Hybrid Graphene Devices





Entanglement?





Hybrid Graphene Devices











Infrastructure

BME:

Low T transport lab: He liquefier, 4 cryostats, He4, He3 systems, electronics, MCBJ, Kerr ...

BME & MFA Joint lab:

E-lithography: JEOL 848 + Raith Elphy; LeoXBeam SEM/FIB, AFM, STM, Clean room (300m²), Raman, ...

Collaboration with L.P. Biro MFA



